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Zhiping Zhou
Changhe Zhou
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Introduction

The tremendous demand on high-density data communications, real time sensing/detection, and high-speed control/actuation has heated up the research and development in micro/nano photonics, which studies the behavior of light on the micro/nanometer scale and deals with high bandwidth, high speed, and ultrasmall optoelectronic components. On the other hand, the micro/nano structures used in micro/nano photonics require highly accurate and reproducible size control, which makes it a great challenge for the fabrication technology.

In this regard, the Micro/Nano Photonics and Fabrication Conference of OIT' 2013 was organized. The conference accepted over 30 papers from different countries/areas of the world, which are focused on the design, fabrication, and application of micro/nanostructures, and crossed many research disciplines including silicon photonics integration, active nanomaterials, metamaterials, nanostructure device, and fabrication technology. During the conference, novel materials, such as carbon nanotube, were discussed, newest fabrication technologies, such as untrafast laser fabrication, were reviewed, and quite a few invited papers showed exciting achievements. It is a great pleasure to see many most recent progresses in micro/nano photonics and fabrication were presented in this conference.

As the committee chairs, we would like to express our appreciation to the committee members for their support, to the presenters for devoting their precious time to write the intriguing articles, and to the reviewers for their helpful comments. We are also grateful to the SPIE staff for their efforts in publishing this Proceedings volume.

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Changhe Zhou

